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<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  <i>(Use as many sheets as necessary)</i>				<i>Application Number</i>	10/541,071
				<i>Filing Date</i>	April 5, 2006
				<i>First Named Inventor</i>	Daniele FACCIO et al.
				<i>Art Unit</i>	2874
				<i>Examiner Name</i>	Kim, Ellen E.
Sheet	1	of	1	<i>Attorney Docket Number</i>	05788.0373-00000

U.S. PATENTS AND PUBLISHED U.S. PATENT APPLICATIONS					
Examiner Initials	Cite No. <sup>1</sup>	Document Number	Issue or Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code <sup>2</sup> (if known)			

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FOREIGN PATENT DOCUMENTS						
Examiner Initials	Cite No. <sup>1</sup>	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	Translation <sup>6</sup>
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NON PATENT LITERATURE DOCUMENTS			
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EK		P.P. Absil et al., "Compact Microring Notch Filters," IEEE Photonics Technology Letters, Vol. 12, No. 4, pp. 398-400, April 2000.	

Examiner Signature	Ellen Kim	Date Considered	10/22/07
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